

FIG. 1 (a)

O: Si (Silicon)

O: H (Hydrogen)

★: O (Oxygen)

Substrate

FIG. 1 (b)

©: Si (Silicon)

O: H (Hydrogen)

★: O (Oxygen) or N (Nitrogen)

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*·O-O-O-O-O-X-O-X-O-X-O-X-O-X-X-X

0-0-0-0-0-0--0-*-0-*-0-*-0-0-0-*

*0-0-0-0-0-0-0--*0-*--*--

Substrate

FIG. 2

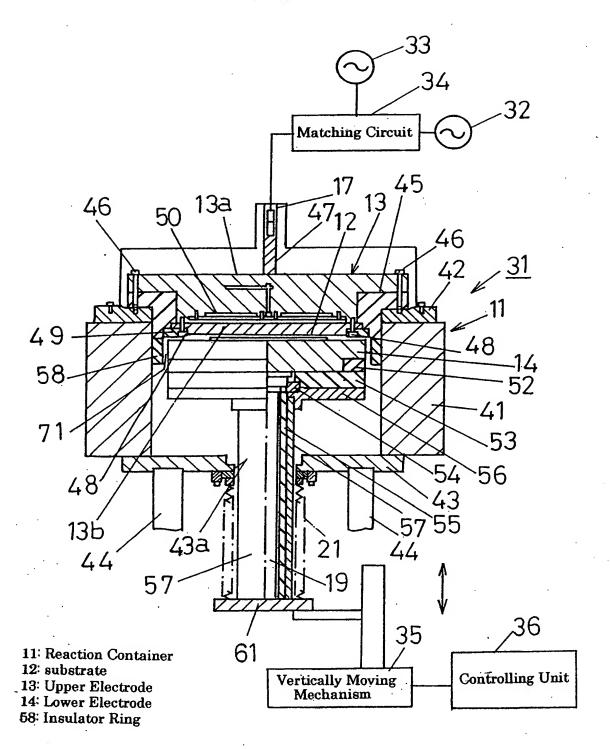


FIG. 3

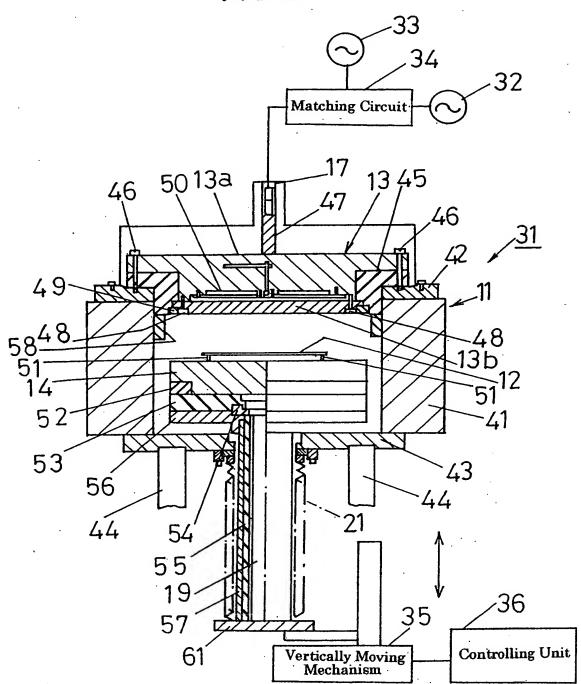


FIG. 4

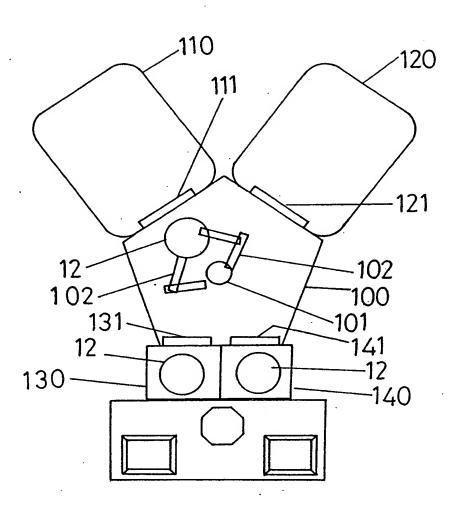


FIG. 5 (prior art)

Pretreatment of Substrate

Growth of Polysilicon Film (up to 1μ m in thickness)

in CVD Equipment

Anodizing Treatment in a Chemical Synthesis Unit